



FORM HDP-1449 (Based on Form PTO-1449)

PATENT AND TRADEMARK OFFICE
INFORMATION DISCLOSURE CITATION
(Use several sheets if necessary)

Sheet 1 of 2

ATTORNEY DOCKET No.	SERIAL No.
25611-000076/US	10/825,199
APPLICANTS	
Se-young JEONG, et al.	
FILING DATE	GROUP
April 16, 2004	Not Yet Assigned

U.S. PATENT DOCUMENTS

Ref. Desig.	Examiner's Initials	Document Number	Date	Name	Class/ Subclass	(If appropriate) Filing Date
	CL	5,837,119	11/17/1998	Kang et al.	—	—
		5,906,312	5/25/1999	Zakel et al.	—	—
		5,674,326	10/7/1997	Wrezel et al.	—	—
		5,958,590	09/28/1999	Kang et al.	—	—
		6,465,879	10/15/2002	Taguchi	—	—
		6,088,236	07/11/2000	Tomura et al.	—	—
		6,028,357	02/22/2000	Moriyama	—	—
		5,431,328	07/11/1995	Chang et al.	—	—
		5,914,536	06/22/1999	Shizuki et al.	—	—
		6,297,562	10/02/2001	Tilly	—	—
		2002/0053467	05/09/2002	Gebauer et al.	—	—
		2001/0054771	12/27/2001	Wark et al.	—	—
	CL	2001/0045668	11/29/2001	Liou et al.	—	—

FOREIGN PATENT DOCUMENTS

Ref. Desig.	Examiner's Initials	Document Number	Date	Country	Class/ Subclass	Translation Yes	No
	CL	2001-0068233	07/23/2001	Korea	—	ABST.	
		2001-0098699	11/08/2001	Korea	—	ABST.	
		2001-0068378	07/23/2001	Korea	—	ABST.	
		2000-0058035	09/25/2000	Korea	—	ABST.	
		2001-0105270	11/28/2001	Korea	—	ABST.	
		1998-0060735	08/23/1999	Korea	—	ABST.	
		2000-091371	03/31/2000	Japan	—	ABST.	
	CL	2002-228707	08/14/2002	Japan	—	ABST.	

Examiner:

calvinlee

Date Considered:

9.28.05

EXAMINER: Please initial if citation considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

FORM HDP-1449 (Based on Form PTO-1449) PATENT AND TRADEMARK OFFICE INFORMATION DISCLOSURE CITATION (Use several sheets if necessary) Sheet 2 of 2	ATTORNEY DOCKET No.		SERIAL No.
	25611-000076/US		10/825,199
	APPLICANT		
	Se-young JEONG, et al.		
	FILING DATE		GROUP
April 16, 2004		Not yet assigned	

	CL	2001-284387	10/12/2001	Japan	—	ABST.	
		2000-232129	08/22/2000	Japan	—	ABST.	
		11-345826	12/14/1999	Japan	—	ABST.	
		2000-241499	09/08/2000	Japan	—	ABST.	
		2001-250889	09/14/2001	Japan	—	ABST.	
		2000-164638	06/16/2000	Japan	—	ABST.	
		11-345900	12/14/1999	Japan	—	ABST.	
		09-129669	05/16/1997	Japan	—	ABST.	
		05-182973	07/23/1993	Japan	—	ABST.	
	CL	08-090285	04/09/1996	Japan	—	ABST.	

OTHER DOCUMENTS (including Author, Title, Date, Pertinent Pages, etc.)		
Ref. Desig.	Examiner's Initials	

Examiner: <i>calvinlee</i>	Date Considered: <i>9.28.05</i>
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<p>FORM HDP-1449 (Based on Form PTO-1449)</p> <p>PATENT AND TRADEMARK OFFICE INFORMATION DISCLOSURE CITATION (Use several sheets if necessary)</p> <p>Sheet 1 of 1</p>	ATTORNEY DOCKET NO.	SERIAL NO.
	25611-000076/US	NEW APPLICATION
	APPLICANTS	
	Se-young JEONG, et al.	
	FILING DATE	GROUP
April 16, 2004	Not yet Assigned	

U.S. PATENT DOCUMENTS						
Ref. Desig.	Examiner's Initials	Document Number	Date	Name	Class/ Subclass	(If appropriate) Filing Date
	CL	US 2001/0054771 A1	12/27/2001	James M. WARK, et al.	_____	_____
	CL	US 2001/0045668 A1	11/29/2001	Fu-tai LIOU, et al.	_____	_____

FOREIGN PATENT DOCUMENTS							
Ref. Desig.	Examiner's Initials	Document Number	Date	Country	Class/ Subclass	Translation Yes	No
	CL	JP 2000-241499	09/08/2000	JAPAN	_____	ABST.	
	CL	JP 11-345826	12/14/1999	JAPAN	_____	ABST.	

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)		
Ref. Desig.	Examiner's Initials	

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